

60. A metal processing system, comprising:

a furnace comprising a quartz tube and configured to house a high-density plasma and to allow deposition of a metal on said quartz tube and on a wafer located inside said quartz tube; and

a cleaning chamber coupled to said furnace and configured to house a gas that is configured to etch said metal from said quartz tube.

61. The system in claim 60, wherein said furnace is configured to allow said gas to access said quartz tube to the exclusion of said wafer.

62. The system in claim 61, wherein said furnace is configured to allow said gas to access said quartz tube in response to a removal of said wafer from said furnace.

#### REMARKS

Claims 41-62 are pending. Applicants submit that they are allowable. If there are any matters that may be resolved or clarified through a telephone interview, the Examiner is requested to contact Applicants' undersigned attorney at the number indicated.

Respectfully submitted,

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